ELECTRON PROBE MICROANALYZER

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Inventor(s): NIWA NAOMASA
Applicant(s): SHIMADZU CORP
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Abstract

PROBLEM TO BE SOLVED: To obtain highly reliable measured data by an electron probe microanalyzer by continuously carrying out a linear analysis and a mapping analysis without breaking down automatic height compensation by automatic focusing, even if the surface shape of a specimen changes.
SOLUTION: This electron probe microanalyzer 1 to analyze an element on the surface of a specimen by characteristic X rays discharged from the specimen by irradiation of an electron beam is equipped with a means of driving a stage 7 to drive an optical focus position detecting device 2 and a specimen stage 6 in the direction of X, Y and Z axes and a means of controlling a driving speed 3 to control the driving speed of the specimen stage 6 in the direction of the X and Y axes in accordance with a focusing signal level from the optical focus position detecting device 2. Thereby, continuous and automatic height compensation by an automatic focusing control is made possible by controlling the driving speed in the directions of the X and Y axes in accordance with a change on the surface of the specimen, and reliability of measured data is enhanced.

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